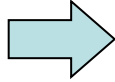


## Characteristics

- High purity
- High Density
- High thermal conductivity



## Features

- Fewer metal contamination on wafers
- Excellent outgas performance and few particles
- Excellent cooling rate and thermal response

## Products

Applications	Products
Plasma Etch system / apparatus	Shower plate, Focus ring etc.
Plasma CVD apparatus , thermal CVD apparatus	Susceptor etc.
Thermal processing apparatus	Susceptor, wafer holder etc.



**Fig.1** Focus ring



**Fig.2** Shower plate